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**SECOND AMENDMENT UNDER 37
CFR 1.116 EXPEDITED PROCEDURE -
EXAMINING GROUP 1763**

Box AF
Assistant Commissioner for Patents
Washington, D.C. 20231

PATENT
Attorney Docket No.: 1771X2T19930
TTC No.: 016301-019930

On April 15, 2002

TOWNSEND and TOWNSEND and CREW LLP

By: [Signature]

#30 HNR
4/29/02
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

SEBASTIEN RAOUX et al.

Application No.: 08/988,246

Filed: December 1, 1997

For: METHOD AND APPARATUS FOR
MONITORING AND ADJUSTING
CHAMBER IMPEDANCE

Examiner: Rudy Zervigon

SECOND AMENDMENT UNDER 37 CFR
1.116 EXPEDITED PROCEDURE
EXAMINING GROUP 1763

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Washington, D.C. 20231

Sir:

In response to the Advisory Action dated March 15, 2002 in the above-identified application, Applicants respectfully request entry of the Amendment under 37 CFR § 1.116 filed on February 11, 2001, as repeated below.

IN THE CLAIMS:

Please amend claims 11, 16, and 20 as follows.

11. A substrate processing system comprising:
a deposition chamber comprising a reaction zone;